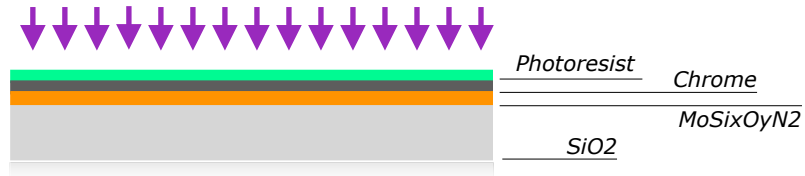
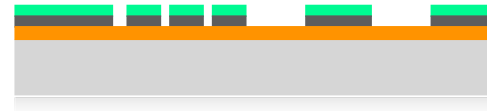


MoSiON Attenuated PSM



1 Pattern exposure



2 Develop resist and (wet) chrome etch



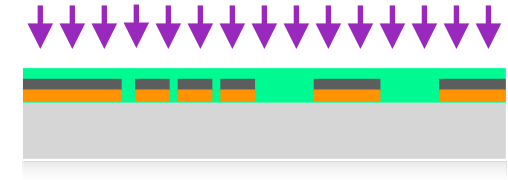
3 Dry (plasma) etch MoSi layer



4 Strip resist



5 Re-coat with resist



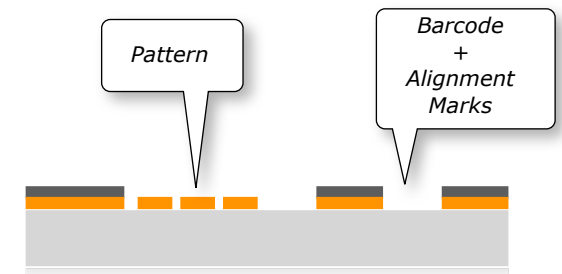
6 Second (bulk) exposure of pattern



7 Develop resist



8 Wet-etch chrome (over main



9 Strip resist to leave chrome